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**(71) Applicant(s):**

SHARP KABUSHIKI KAISHA [JP/JP]; 1, Takumi-cho, Sakai-ku, Sakai City, Osaka 5908522 (JP) *(for all designated states)*

**(72) Inventor(s):**

KANEKO, Seiji

KANZAKI, Yohsuke

SAITOH, Takao

MIWA, Masahiko

YAMANAKA, Masaki

**(74) Agent(s):**

HARAKENZO WORLD PATENT & TRADEMARK; Daiwa Minamimorimachi Building, 2-6, Tenjinbashi 2-chome Kita, Kita-ku, Osaka-shi, Osaka 5300041 (JP)

**(54) Title (EN):** INFLEXIBLE SUBSTRATE PROVIDED WITH DISPLAY ELEMENT, AND FLEXIBLE DISPLAY DEVICE MANUFACTURING METHOD

**(54) Title (FR):** SUBSTRAT RIGIDE POURVU D'UN ÉLÉMENT D'AFFICHAGE, ET PROCÉDÉ DE FABRICATION DE DISPOSITIF D'AFFICHAGE SOUPLE

**(54) Title (JA):** 表示素子を備えた非可撓性基板及び可撓性表示装置の製造方法

**(57) Abstract:**

**(EN):** In a right-side PI layer inclined area (RPA), a photosensitive PI layer (10), which covers a ground PI layer (2) exposed from an inorganic film composed of a moisture-proof layer (3), a gate insulation layer (5), a second insulation layer (7), and a third insulation layer (9), is formed.

**(FR):** Selon la présente invention, dans une zone inclinée de couche PI côté droit (RPA), une couche PI photosensible (10), qui recouvre une couche PI de mise à la terre (2) visible au niveau d'un film inorganique composé d'une couche étanche à l'humidité (3), d'une couche d'isolation de grille (5), d'une deuxième couche d'isolation (7) et d'une troisième couche d'isolation (9), est formée.

**(JA):** 右側PI層傾斜領域(RPA)においては、防湿層(3)とゲート絶縁層(5)と第2絶縁層(7)と第3絶縁層(9)との無機膜から露出する下地PI層(2)を覆う感光性PI層(10)が形成されている。

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